

Trion ICP/RIE Plasma Etcher

- Etching of **SiO₂**, **Si₃N₄**, **Glass**, **Si**
- Gases: N₂, Ar, O₂, CF₄, SiCl₄, SF₆
- Samples : Pieces – 4" Wafer
- Allowed Masking Materials: Photoresists or Silicon Mask
- Load-lock capability

